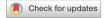
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OPEN Author Correction: Influence of plasma treatment on SiO₂/ Si and Si₃N₄/Si substrates for large-scale transfer of graphene

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The original version of this Article omitted an affiliation for M. Lisker. The correct affiliations for M. Lisker are listed below:

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The original Article and accompanying Supplementary Information file have been corrected.

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